Silicon Compatible Emerging Materials, Processes, and Technologies for Advanced CMOS and Post-CMOS Applications 14

Editors:

- H. Jagannathan
- P. J. Timans
- F. Roozeboom

Sponsoring Divisions:



Electronics and Photonics



Dielectric Science and Technology



Published by

The Electrochemical Society 65 South Main Street, Building D Pennington, NJ 08534-2839, USA tel 609 737 1902 fax 609 737 2743 www.electrochem.org

ecstransactions **

Vol. 113, No. 5

Copyright 2024 by The Electrochemical Society. All rights reserved.

This book has been registered with Copyright Clearance Center. For further information, please contact the Copyright Clearance Center, Salem, Massachusetts.

Published by:

The Electrochemical Society
65 South Main Street
Pennington, New Jersey 08534-2839, USA

Telephone 609.737.1902 Fax 609.737.2743 e-mail: ecs@electrochem.org Web: www.electrochem.org

ISSN 1938-6737 (online)

ISBN 978-1-62332-673-9 (PDF)

Printed in the United States of America.

ECS Transactions, Volume 113, Issue 5

Silicon Compatible Emerging Materials, Processes, and Technologies for Advanced CMOS and Post-CMOS Applications 14

Table of Contents

Preface	iii
A New Integration Scheme to Prevent Chemical Attack on Floating Polysilicon Gate of Non-Volatile Memory Y. Yang, K. F. Kong, Y. W. Teh, G. Zhou, N. Yu, K. Yu	3
Unveiling Sub-60 mV/decade Subthreshold Swing in The Oxide Local Thinning (OLT) Gated MIS Tunnel Diodes by TCAD Simulations S. W. Huang, J. Y. Lin, J. G. Hwu	9
Author Index	19